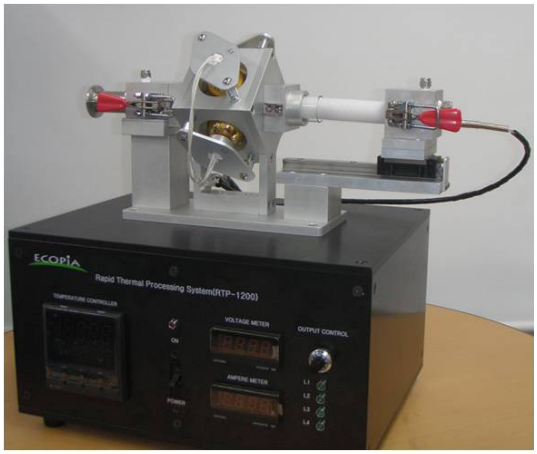
RTP1200
RAPID THERMAL PROCESSING SYSTEM

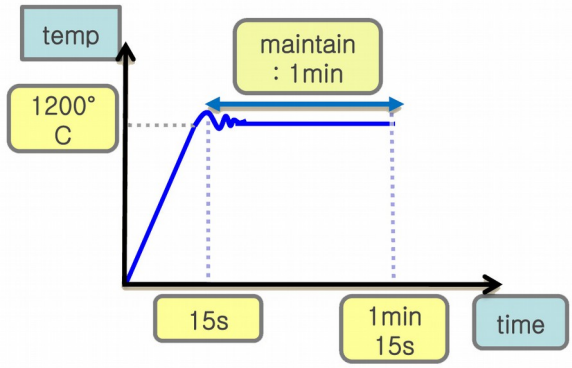


Our RTP1200 model is very easy and powerful RTP system to increase very high temperature by using 4 tungsten-halogen lamp.

Researcher in the lab and university can get accurate test data by simple and easy installation and operation.

We recommend to use the researcher who is interested in getting RTP system, easy to install and use to convenient and powerful to perform and reasonable price.

- Heat treatment in high vacuum
- Heat treatment in ambient atmosphere
- High accuracy temperature control
- No need additional cooling system
- Compact desktop design
- Reasonable price



Application:

1) Thin film deposition
2) Oxidize thin film on the sample.
3) Construction analysis of thin film at high temperature
4) Paste material analysis
5) Ohmic contact formation by .i.e Ag.Au electrical conductivity material.
6) Heat treatment after ion implantation and activating ion implantation.
7) Melting point analysis of alloy.

Characteristics:

1) Easy to do thermal treatment in vacuum status, purge gas flow and at ambient atmosphere.
2) No need additional cooling system by attaching IR reflective panel and minimize radiant heat

3) Very convenient to load and unload tested material by simple manipulation.

4) Compact desktop design and convenient to move and install.

5) Accurate temperature control by temperature sensor which was attached in sample loading stage.

6) Possible to use this model as furnace capability of +/- 3°c accuracy.

7) CE certified

Specifications:

	Specification	Unit	Remark
Max sample size	15 x 15 or 15 x 20	mm	
Maximum rising speed	100	°C/sec	
Maximum cooling speed	50	sec	1000°C → 400°C
Cooling speed		sec	400°C → RT
Max temperature	1200	°C	
Temperature accuracy	+/- 0.3	°C	@1000°C
Lamp power	600	W	Hallogen Lamp 4pcs
Size	40 x 30 x 45	cm	
Weight	30	Kg	
Maximum power	800	W	
Maximum amperage	80	A	
Frequency	50/60	Hz	
Voltage rate	220, single phase	V	
Lamp current rate	40	A